

2017 Source Workshop (November 6-8, 2017), Dublin, Ireland

Session	#	Presenter	Company	Title	Oral / Poster
Keynote	S1	Carolyn Larabell	LBL	Imaging biological cells using soft x-ray tomography	O
Keynote	S2	Igor Fomenkov	ASML	EUV Source for High Volume Manufacturing: Performance at 250 watt, and Key Technologies for Power Scaling	O
Fundamental Data	S11	James Colgan	LANL	Atomic data of low-charged Sn ions for lithography applications	O
Fundamental Data	S12	Noboyuki Nakamura	UEC Tokyo	EUV spectra of highly charged ions observed with a compact electron beam ion trap	O
Fundamental Data	S13	Hendrik Bekker	Max Planck Institute	Fundamental studies of $\text{Sn}^{7+}$ - $\text{Sn}^{14+}$ ions with applications for laser produced plasma sources	O
Fundamental Data	S14	Ronnie Hoekstra	ARCNL	Tin ion spectroscopy on plasma sources of EUV light	O
Modeling	S21	Bowen Li	Lanzhou University	Atomic and radiative processes in high-Z plasmas and their applications in EUV Lithography and “Water Window” imaging	O
Modeling	S22	Howard Scott	LLNL	Towards High-Fidelity Simulations of EUV Production from Laser-Produced Plasma	O
Modeling	S23	John Shiel	UCD	Soft x-ray spectroscopy of Dy, Er and Tm ions excited in laser-produced plasmas	O
Modeling	S24	Akira Sasaki	QST	Modeling of particle debris from the target of laser pumped plasma EUV source	O

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Modeling	S25	Slava Medvedev	ISAN	Measurements and numerical simulations of Sn ion stopping in low-pressure H <sub>2</sub> atmosphere	P
Modeling	S26	Luning Liu	UCD	Configuration Interaction Effects in Unresolved np <sup>6</sup> nd <sup>N+1</sup> -np <sup>5</sup> nd <sup>N+2</sup> +np <sup>6</sup> nd <sup>N</sup> nf <sup>1</sup> Transition Arrays; Contrasting Behaviour for n=4 and n=5	P
Lasers	S31	Thomas Metzger	Trumpf	High Average Power and High Energy Ultrafast Thin-Disk Amplifiers	O
Lasers	S32	Johannes Weitenberg	Max-Planck Institute of Quantum Optics	High-harmonic generation for metrology applications	O
Lasers	S33	Jiri Muzi	HiLase	Development of kW-level picosecond thin-disk pre-pulse laser for high-power EUV sources	O
Lasers	S34	Mira Vrbova	Czech Academy for Sciences	Modelling of hybrid pumping of nitrogen recombination laser	P
LPP-HVM	S41	Hakaru Mizoguchi	Gigaphoton	High Power LPP-EUV Source with Long Collector Mirror Lifetime for High Volume Semiconductor Manufacturing	O
LPP-HVM	S42	Kentaro Tomita	Kyushu University	Two-dimensional electron density and temperature profiles of EUV light sources with 4.0% CE	O
LPP-HVM	S43	Francesco Torretti	ARCNL	Short-wavelength out-of-band EUV emission from Sn laser-produced plasma	O
LPP-HVM	S44	Dmitry Kurilovich	ARCNL	Expansion dynamics after laser-induced cavitation in liquid tin microdroplets	P

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LPP-HVM	S45	Thomas Morgan	DIFFER	Vapour shielding of tin under intense plasma bombardment	O
LPP-HVM	S46	Oscar Versolato	ARCNL	ARCNL Project Overview (Tentative Title)	O
LPP-HVM	S47	Yuta Sato	Kyushu University	Development of a collective Thomson scattering system for laser-produced high-Z plasmas for soft X-ray light sources	P
Metrology Sources	S51	Yusuke Teramoto	Ushio	Characterization of laser-assisted and laser-driven EUV sources for metrology applications	O
Metrology Sources	S52	Duane Hudgins	ETHZ	Laser induced shockwave droplet breakup dynamics	O
Metrology Sources	S53	Klaus Bergmann	Fraunhofer	Plasma based XUV sources for metrology applications	O
Metrology Sources	S54	Yasin Ekinici	PSI	A high-brightness accelerator-based EUV source for EUV actinic mask inspection	O
Metrology Sources	S55	Samir Ellwi	ISTEQ	Actinic light source based on LPP for HVM mask inspection applications	O
Metrology Sources	S56	Joe Kline	NIST	Compact X-ray Sources and Applications for Semiconductor Metrology	O
Metrology Sources	S57	Oisín Maguire	UCD	EUV/SXR spectroscopy of Ge Laser-Produced Plasma: Ge VI-XI in the 9-18 nm region	P

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Metrology Sources	S58	Domagoj Kos	UCD	Colliding laser produced plasmas analysis: fast imaging and spectroscopic study	P
Broad Band EUV Sources	S61	Vivek Bakshi	EUV Litho	Industry Requirements for Broad Band EUV Sources for Wafer Inspection Applications	O
Broad Band EUV Sources	S62	Steve Horne	Energetiq	The Electrode-less Z-Pinch as a metrology source in the 40-50 nm range.	O
Broad Band EUV Sources	S63	Ilya Bezel	KLA	High Power Laser-Sustained Plasma Light Sources for KLA-Tencor Broadband Wafer Inspection Tools	O
Broad Band EUV Sources	S64	Samir Ellwi	ISTEQ	High brightness broadband light source for various industrial applications	P
EUV /XUV Applications	S71	Gerry McDermott	LBL	Soft X-ray Microscopes for Biology: The Source	O
EUV /XUV Applications	S72	Maija Vihinen-Ranta	Finland	Chromatin reorganization during viral infection	O
EUV /XUV Applications	S73	Fergal O'Reilley	UCD	Exploring the Soft X-ray Radiance of Laser Plasmas	O
EUV /XUV Applications	S74	Daniel Vicario	ILT	Laboratory tomographic microscopy with compact plasma based extreme ultraviolet and soft x-ray sources	P
EUV /XUV Applications	S75	Brendan Dromey	Queen's University Belfast	Relativistic plasma control using two-colour fields	O

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EUV /XUV Applications	S76	Larissa Juschkin	ILT	Spectroscopic EUV reflectometry for characterization of thin films systems and determination of optical constants	O
Optics and Metrology	S81	Torsten Feigal	OptixFab	REFURBISHMENT OF COLLECTOR MIRRORS FOR WATER WINDOW MICROSCOPY	O
Optics and Metrology	S82	Eric Louis	Univ Twente	EUVL optics for Free Electron Laser sources: damage threshold studies and the use of adjusted wavelengths	O
Optics and Metrology	S84	Slava Medvedev	ISAN	Novel spectrometers for broad-band characterization of EUV-emitting plasmas	O
Optics and Metrology	S85	Muharrem Bayraktar	Univ. Twente	Broadband spectral characterization of EUV light sources with a transmission grating spectrometer	O
Optics and Metrology	S86	Carmen Vela Garcia	UCD	An EUV Monochromator for use with an LPP Source	P